

## (12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property Organization

International Bureau



(43) International publication date

9 September 2005 (09.09.2005)

PCT

(10) International publication number

WO 2005/083511 A2

(51) International patent classification<sup>7</sup>:

G03F

(74) Attorney: LORENZ, Werner; Alte Ulmer Strasse 2, 89522 Heidenheim (DE).

(21) International application number: PCT/EP2005/001797

(22) International filing date: 22 February 2005 (22.02.2005)

(25) Language of filing: German

(26) Language of publication: German

(30) Data relating to the priority:

10 2004 009 239.7 26 February 2004 (26.02.2004) DE

(71) Applicant (for all designated States except US): CARL ZEISS SMT AG [DE/DE]; Carl-Zeiss-Strasse 22, 73447 Oberkochen (DE)

(72) Inventors; and

(75) Inventors/Applicants (US only): DIECKMANN, Nils [DE/DE]; Reuteweg 5, 73460 Hüttlingen (DE). MAUL, Manfred [DE/DE]; Elchweg 29, 73434 Aalen (DE). FIOŁKA, Damian [DE/DE]; Adalbert-Stifter-Weg 14, 73447 Oberkochen (DE).

(81) Designated states (unless otherwise indicated, for every kind of national protection available): AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SM, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW.

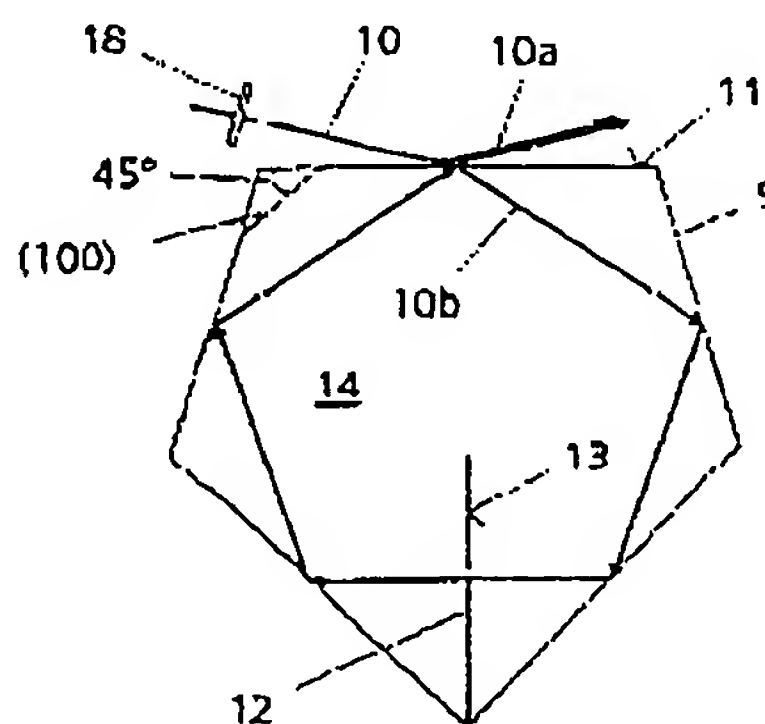
(84) Designated states (unless otherwise indicated, for every kind of regional protection available): ARIPO (BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

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As printed

(54) Title: SYSTEM FOR REDUCING THE COHERENCE OF LASER RADIATION

(54) Bezeichnung: SYSTEM ZUR REDUZIERUNG DER KOHÄRENZ EINER LASERSTRAHLUNG



(57) Abstract: The invention relates to a system for reducing the coherence of a wave front-emitting laser radiation (10b), especially for a projection lens for use in semiconductor lithography, wherein a first partial beam (10a) of a laser beam (10) incident on a surface (11) of a resonator body (9) is partially reflected. A second partial beam (10b) penetrates the resonator body (9) and emerges from the resonator body (9) at least approximately in the area of entry after a plurality of total internal reflections. The two partial beams (10a and 10b) are then passed on jointly to an illumination plane. The resonator body (9) is adapted, in addition to splitting the laser beam into partial beams (10a, 10b), to modulate the wave fronts of at least one partial beam (10b) during a laser pulse. The partial beams (10a, 10b) reflected on the resonator body (9) and penetrating the resonator body are superimposed downstream of the resonator body (9). The resonator body (9, 9') is provided with a phase plate (12) having different local phase distribution.

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EV832834878

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- as to applicant's entitlement to claim the priority of the earlier application (Rule 4.17(iii)) for all designated states
- of inventorship (Rule 4.17(iv)) for the following designation US

**Published:**

- without international search report and to be republished upon receipt of that report

For an explanation of the two-letter codes and the other abbreviations, reference is made to the explanations ("Guidance Notes on Codes and Abbreviations") at the beginning of each regular edition of the PCT Gazette

(57) **Zusammenfassung:** Bei einem System zur Reduzierung der Kohärenz einer wellenförmigen auskennenden Laserstrahlung (10b), insbesondere für ein Projektionsobjektiv in der Halbleiterlithographie wird ein von dem auf eine Oberfläche (11) eines Resonatorkörpers (9) auftreffenden Laserstrahles (10) ein erster Teilstrahl (10a) teilreflektiert. Ein zweiter Teilstrahl (10b) tritt in den Resonatorkörper (9) ein und tritt nach mehreren Totalreflexionen wenigstens annähernd im Bereich der Eintrittsstelle wieder aus dem Resonatorkörper (9) aus. Anschließend werden die beiden Teilstrahlen (10a und 10b) gemeinsam zu einer Beleuchtungsebene weitergeleitet. Der Resonatorkörper (9) ist derart ausgebildet, dass zusätzlich zu der Aufteilung in Teilstrahlen (10a, 10b) die Wellenfronten wenigstens eines Teilstrahles (10b) während eines Laserpulses moduliert werden, wobei die an dem Resonatorkörper (9) reflektierten und die in den Resonatorkörper eintretenden Teilstrahlen (10a, 10b) nach dem Resonatorkörper (9) überlagert werden und wobei der Resonatorkörper (9,9') mit einer Phasentafel (12) mit unterschiedlicher lokaler Phasenverteilung versehen ist.

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